

|                                   |                                       |   |             |
|-----------------------------------|---------------------------------------|---|-------------|
| <b>Notice of References Cited</b> | Application/Control No.<br>10/509,370 | Applicant(s)/Patent Under<br>Reexamination<br>SUGAWARA ET AL. |             |
|                                   | Examiner<br>Eric B. Chen              | Art Unit<br>1765  | Page 1 of 1 |

**U.S. PATENT DOCUMENTS**

| * |   | Document Number<br>Country Code-Number-Kind Code | Date<br>MM-YYYY | Name            | Classification |
|---|---|--|-----------------|-----------------|----------------|
| * | A | US-2002/0009892                                  | 01-2002         | COHEN et al.    | 438/710        |
| * | B | US-6,451,641                                     | 09-2002         | Halliyal et al. | 438/200        |
|   | C | US-  |                 |                 |                |
|   | D | US-  |                 |                 |                |
|   | E | US-  |                 |                 |                |
|   | F | US-  |                 |                 |                |
|   | G | US-  |                 |                 |                |
|   | H | US-  |                 |                 |                |
|   | I | US-  |                 |                 |                |
|   | J | US-  |                 |                 |                |
|   | K | US-  |                 |                 |                |
|   | L | US-  |                 |                 |                |
|   | M | US-  |                 |                 |                |

**FOREIGN PATENT DOCUMENTS**

| * |   | Document Number<br>Country Code-Number-Kind Code | Date<br>MM-YYYY | Country | Name | Classification |
|---|---|--|-----------------|---------|------|----------------|
|   | N |  |                 |         |      |                |
|   | O |  |                 |         |      |                |
|   | P |  |                 |         |      |                |
|   | Q |  |                 |         |      |                |
|   | R |  |                 |         |      |                |
|   | S |  |                 |         |      |                |
|   | T |  |                 |         |      |                |

**NON-PATENT DOCUMENTS**

| * |   | Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)        |
|---|---|--|
|   | U | Wolf, Silicon Processing for the VLSI Era, 2002, Lattice Press, Vol. 4, pp. 145-46.              |
|   | V | Rossnagel et al., Handbook of Plasma Processing, 1990, Noyes Publications, p. 198.               |
|   | W | Kern, Handbook of Semiconductor Wafer Cleaning Technology, 1993, Noyes Publications, pp. 224-26. |
|   | X |  |

\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.